

SHEET 1 OF 1

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION		APPLICANT(S) Mark L. Jones et al.				
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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
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/B.R./	5,804,981	9/8/1998	Lowell et al.			
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FOREIGN PATENT DOCUMENTS						
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/B.R./ ✓	M. B. Shabani, <i>Kinetic of Low-Temperature Out-Diffusion of Cu from Silicon Wafers</i> , Abstract No. 1389, submitted to ECS in Oct. 1999					
/B.R./ ✓	Shabani, M., and Okuuchi, S., <i>Effect of Dopants and Oxygen Precipitation on Low-Temperature Out-Diffusion and Gettering of Cu in Silicon Wafer</i> , Proceedings of Seventh International Symposium on Silicon-on-Insulator Technology and Devices, published by The Electrochemical Society, 96-3, 10 (1997)					
/B.R./ ✓	C.M. McCarthy et al., <i>Room Temperature Copper Out-Diffusion from the Bulk of Silicon Wafers and its Behavior Following Various Postanneal Treatments</i> , ECS Proc. 98-1, 629-640 (1998)					
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